

METHOD FOR UNPATTERNED RESIST ETCH BACK
OF SHALLOW TRENCH ISOLATION REFILL INSULATOR

ABSTRACT OF THE DISCLOSURE

5 A method for forming shallow trench isolation
structures is provided that includes forming a plurality of
isolation trenches (32) in a substrate (10) where the
isolation trenches (32) separate active areas (18). An
insulation layer (44) is formed outwardly from the
substrate (10) with the insulation layer (44) filling the
isolation trenches (32) and covering the active areas (18).
A planarization layer (46) is formed outwardly from the
insulation layer (44). The planarization layer (46) and
the insulation layer (44) are removed together at a
substantially even rate down to a polish stop (14) outward
from the active areas (18).

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